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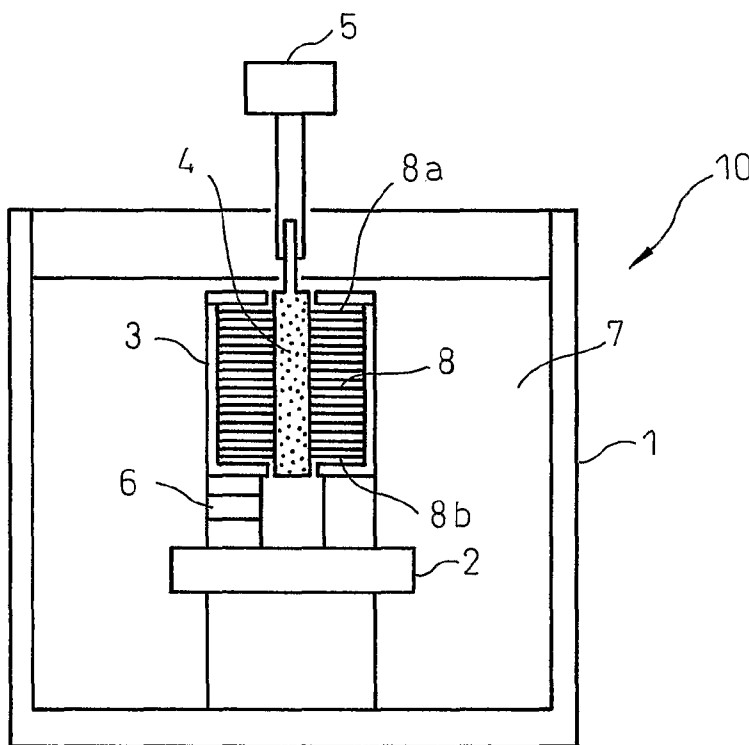
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(54) Title: METHOD OF POLISHING THE INNER PERIPHERAL END SURFACES OF SUBSTRATES FOR A RECORDING MEDIUM USING A BRUSH



(57) Abstract: A polishing method without dispersion in the amount of working at the time of polishing the inner peripheral end surfaces of a plurality of disk-like substrates for a recording medium is provided. There is provided a method of polishing the inner peripheral end surfaces of disk-like substrates for a recording medium using a brush comprising, providing a plurality of pieces of disk-like substrates for a recording medium having a circular hole at the central portion thereof thereby forming an inner peripheral end surface, and stacking them while aligning the circular holes to form an object to be polished having the circular hole at the central portion thereof; bringing a polishing material slurry containing a polishing material into contact with the object to be polished; inserting a polishing brush having brush hairs studded on the periphery of a rod-like shaft into the circular hole of the object from a first side of the object to be polished in a state where the slurry is brought into contact with the object to be polished, and rotating the polishing brush with the shaft as a center to polish the inner peripheral end surfaces of the substrates; and inserting the polishing brush into the circular hole of the object to

be polished from a second side opposite to the first side in a state where the slurry is brought into contact with the object to be polished, and rotating the polishing brush with the shaft as a center axis to polish the inner peripheral end surfaces of the substrates.



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